EQUIVDOC INC 'J62269140'

****** Item Number 1 of 1 ******

DESCRIP :: PATENT

TITLE :: Three-layered pattern formation - includes coating base with organic high molecular cpd., coating with mixt. of organosilane hydrolyzate and colloidal silica and/or silane,

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DATE :: Nov 21, 1987

ABSTRACT :: < BASIC> JP62269140 Method includes (a) coating the uneven base surfac with the organic high molecular cpd. to make a flat surface, (b) coating the organic high molecular cpd. with the coating agent obtd. by mixing the hydrolyzate of organosilano cpd. of formula: R1Si(OR2)3 (R1 is 1-8C organic gp.; R2 is 1-5C alkyl or 1-4C acyl), and colloidal silica and/or silane cpd. of formula Si(OR2)4 or its polycondensate of the water and hydrophilic organic solvent, or coating agent obtd. by mixing at least one silane cpd., its hydrolyzate and partial polycondensate of the hydrolyzate, and at least one zirconium cpd. of formula Zr(OR2)4, hydrolyzate of zirconium cpd. and partial polycondensate of the hydrolyzate, (c) hardening the coating agent to form a hardened film, (d) forming a resist pattern onto the hardened film, (e) etching the hardened film while using the resist pattern as the mask, and transferring the pattern onto the hardened film, and (f) etching the organic high molecular cpd. film while using the hardened film pattern as the mask. ADVANTAGE - The three-layered structure can be stably mfd., and the pattern of upper layer resist can be accurately transferred onto the high molecular cpd. film. @(9pp Dwg.No.0/0)@

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